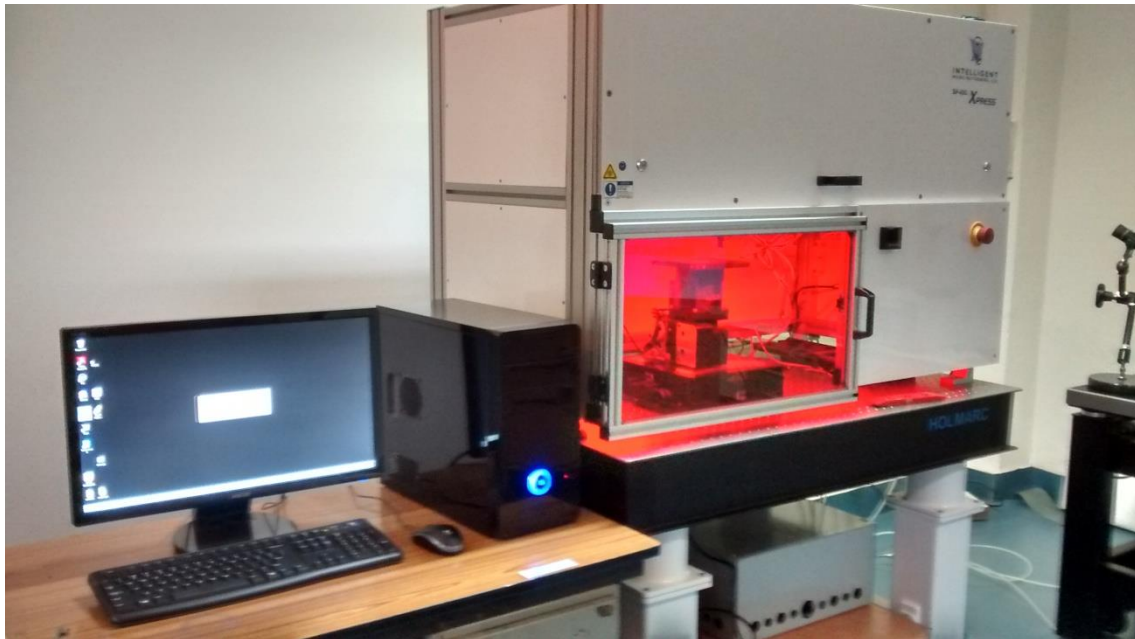


Measurement of: Fabrication of sub-micron lithographic patterns

Equipment: Maskless lithography

Photograph (small size)



Basic Principle:

The system is ideally suited for photomask fabrication or other standard lithography processes, such as SU8 or resist patterning. System is suitable for fabricating low resolution patterns (resolution > 15 micron).

Capabilities: Photolithography system Low resolution patterning, minimum feature size >10 Micron, resolution >15 micron Lithography on photoresist coated substrate, mask preparation

Sample Requirement: Design to be patterned in bmp or DXF format, sample size < 6 inch wafer